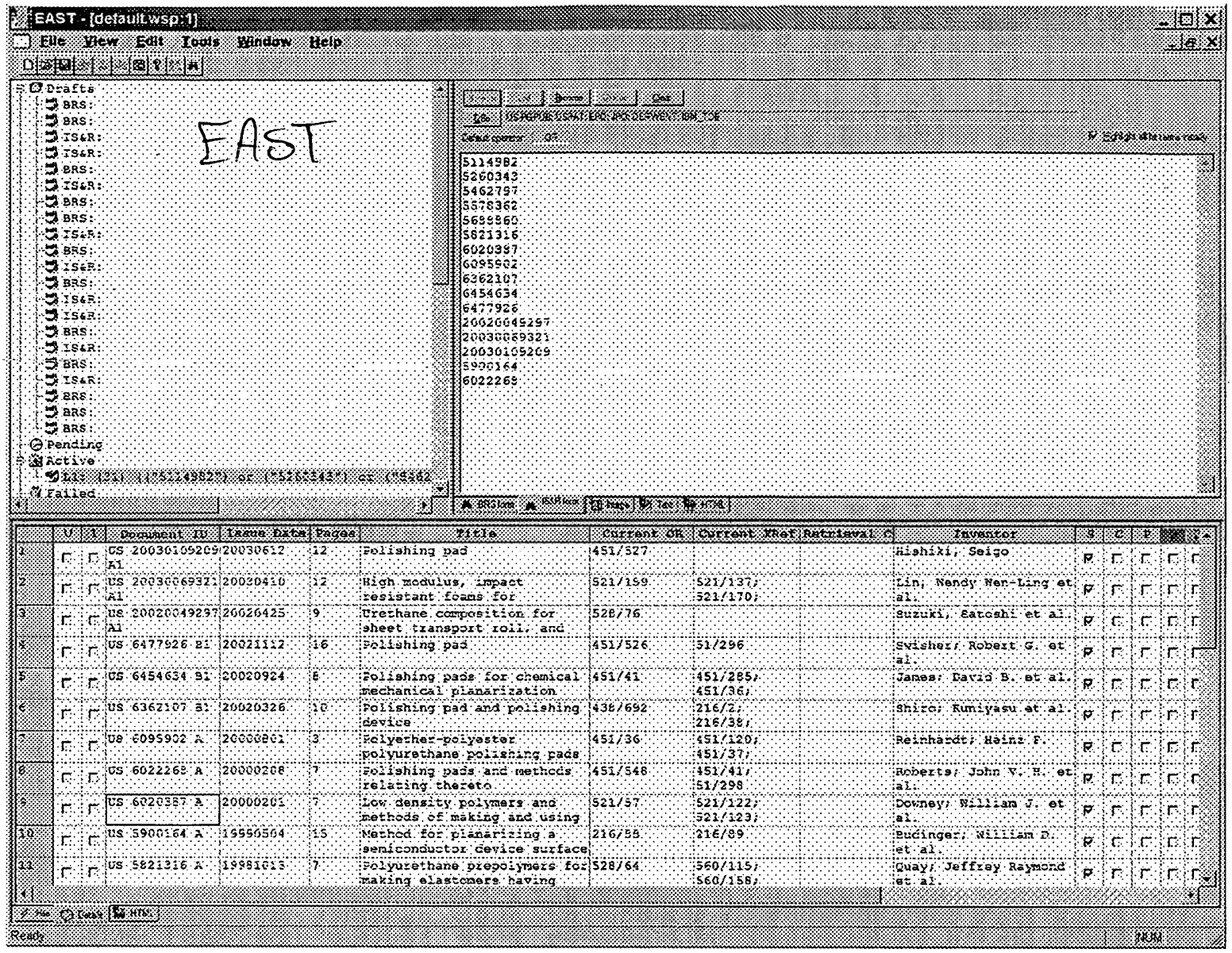

	V	1	Document ID	Issue Date	Pages	Title	Current OR	Current XRef	Retrieval C	Inventor	#	C	P		
1	☐	☐	US 20030109209 A1	20030612	12	Polishing pad	451/527			Hishiki, Seigo	P	☐	☐	☐	☐
2	☐	☐	US 20030069321 A1	20030410	12	High modulus, impact resistant foams for	521/159	521/137; 521/170;		Lin, Nendy Nen-Ling et al.	P	☐	☐	☐	☐
3	☐	☐	US 20020049297 A1	20020425	9	Urethane composition for sheet transport roll, and	528/76			Suzuki, Satoshi et al.	P	☐	☐	☐	☐
4	☐	☐	US 6477926 B1	20021112	16	Polishing pad	451/526	51/296		Svisher, Robert G. et al.	P	☐	☐	☐	☐
5	☐	☐	US 6454634 B1	20020924	8	Polishing pads for chemical mechanical planarization	451/41	451/285; 451/36;		James; David B. et al.	P	☐	☐	☐	☐
6	☐	☐	US 6362107 B1	20020326	10	Polishing pad and polishing device	438/692	216/2; 216/38;		Shiro; Kumiyasu et al.	P	☐	☐	☐	☐
7	☐	☐	US 6095902 A	20000801	3	Polyether-polyester polyurethane polishing pads	451/36	451/120; 451/37;		Reinhardt; Heinz F.	P	☐	☐	☐	☐
8	☐	☐	US 6022268 A	20000208	7	Polishing pads and methods relating thereto	451/548	451/41; 51/298		Roberts; John V. H. et al.	P	☐	☐	☐	☐
9	☐	☐	US 6020387 A	20000201	7	Low density polymers and methods of making and using	521/57	521/122; 521/123;		Downey; William J. et al.	P	☐	☐	☐	☐
10	☐	☐	US 5900164 A	19990504	15	Method for planarizing a semiconductor device surface	216/88	216/89		Budinger; William D. et al.	P	☐	☐	☐	☐
11	☐	☐	US 5821316 A	19981013	7	Polyurethane prepolymers for making elastomers having	528/64	560/115; 560/158;		Quay; Jeffrey Raymond et al.	P	☐	☐	☐	☐